

SEC.492

Abstract of the Disclosure

A chemical for dissolving a sample taken from the semiconductor device fabrication equipment for analyzing the contaminants attached thereon, and a method of analyzing the contaminants thereby. The chemical composition is made of equal parts of sulfuric acid, hydrogen fluoride, and nitric acid. The method includes a) immersing a sample taken from semiconductor device fabrication equipment in the chemical composition; b) dissolving the sample in the chemical composition; c) cooling the dissolved sample; d) diluting the dissolved sample with deionized water and e) analyzing the diluted sample using either Atomic Absorption Spectrometer or by Atomic Emission Spectroscopy.

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